

REMARKS

Applicant has amended the pending claims to clarify the invention and believes that the claims are patentable over the rejections of record. The Examiner has identified a number of references that have served as the basis of rejections under 35 U.S.C. §§ 102 and 103. Applicant believes these rejections are misplaced, and notes that the claimed invention is directed to a method of laminating a photoresist sheet to a substrate. In a first embodiment, the method includes providing a photoresist sheet; providing a preformed adhesive sheet; providing a substrate (such as glass to be etched); applying the adhesive sheet to the substrate; and applying the photoresist sheet to the substrate to form a composite structure containing the photoresist sheet, adhesive sheet, and substrate.

In a second aspect, the invention is directed to a method of laminating a photoresist sheet to a substrate. The method includes providing a photoresist sheet; providing a preformed adhesive sheet; providing a substrate; applying the adhesive sheet to the photoresist sheet; and applying the photoresist sheet to the substrate to form a composite structure containing the photoresist sheet, adhesive sheet, and substrate. Use of the preformed adhesive sheet is advantageous because it allows the photoresist sheet or mask to be applied quickly and without mess. In addition, the thickness of the adhesive sheet can be controlled so as to prevent formation of excessively thick areas or areas of irregular thickness that inhibit uniform abrasive blasting.

The Examiner has rejected the limitations of claim 4, now incorporated into claim 1, on the basis that Etter et al. (U.S. Patent No. 4,115,125A) teaches the claimed invention. Applicant respectfully disagrees. Etter is not directed to a photoresist sheet, but merely to photographic elements such as in the phototypesetting industry. Etter uses an adhesive to adhere photographic elements to a paper support, in contrast to the present invention where the adhesive secures the photoresist sheet to a substrate, and is subsequently exposed to surface abrasion. Generally, the adhesive should provide sufficient strength between the photoresist mask layer and the substrate's target surface to prevent the abrasive decorating process from blasting away portions of the photoresist mask. In addition, when the photoresist mask is a laminate comprising a plurality of layers, some of which are removed after adhering of the laminate to the target surface, the adhesion between the photoresist mask layer and the target surface provided by the adhesive should be greater than the adhesion between any release liner and layer of the

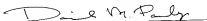
photoresist laminate which is in contact with the photoresist mask layer. This may be called the "transferability" of the photoresist mask. Nothing in Etter discloses any of these aspects of photoresist masks or the properties of materials used to adhere them to a substrate.

In view of the above amendments and remarks, Applicant respectfully requests a Notice of Allowance. If the Examiner believes a telephone conference would advance the prosecution of this application, the Examiner is invited to telephone the undersigned at the below-listed telephone number.

Respectfully submitted,

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